

STRUCTURE AND METHOD FOR SHADOW MASK ELECTRODE

ABSTRACT

A method and structure for an electrode device, whereby a second electrode is deposited on a first electrode such that there is an increase in the capacitive coupling between the pair of conductive electrodes. The electrodes are self-aligning such that the patterning manufacturing process is insensitive to variations in the positional placement of the pattern on the substrate.

Moreover, a single lithographic masking layer is used for forming the pair of electrodes, which are electrically isolated. Finally, the first electrode is offset from the second electrode by a chemical surface modification of the first electrode, and an anisotropic deposition of the second electrode which is shadowed by the first electrode.